

# Journal of Vacuum Science & Technology A

## Vacuum, Surfaces, and Films



# JVST A

Second Series  
Volume 31, Number 1  
Jan/Feb 2013

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*Journal of Vacuum Science & Technology A* (ISSN: 0734-2101) is published six times annually (Jan/Feb, Mar/Apr, May/Jun, Jul/Aug, Sep/Oct, Nov/Dec) by AVS through the American Institute of Physics, Suite 1NO1, 2 Huntington Quadrangle, Melville, NY 11747-4502. 2013 subscription rates are: US\$1720. POSTMASTER: Send address changes to *Journal of Vacuum Science & Technology A*, Membership Services, AVS, 125 Maiden Lane, 15th Floor, New York, NY 10038, membership@avs.org, www.avs.org. Periodicals postage paid at Huntington Station, NY 11746, and at additional mailing offices.

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**On The Cover:** Frank Greer, Erika Hamden, Blake C. Jacquot, Michael E. Hoenk, Todd J. Jones, Matthew R. Dickie, Steve P. Monacos, and Shouleh Nikzad, JVST A, 31(1), p. 01A103-3 (2013). Cover shows diffracted and transmitted images of a fiber optic lamp passing through a thinned Cassini CCD imager (10 microns thick).